

<b>Notice of References Cited</b>	Application/Control No. 10/533,890		Applicant(s)/Patent Under Reexamination PERSOONE ET AL.	
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#### U.S. PATENT DOCUMENTS

* A B C D E F G H I J K L M	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	US-			
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#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

* U V W X	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	K. Okimura "Low temperature growth of rutile TiO <sub>2</sub> films in modified rf magnetron sputtering", Surface and Coatings Technology, Volume 135, Issues 2-3, 15 January 2001, Pages 286-290

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.